

Structural and optical properties of lead iodide nanostructure synthesized by vacuum evaporation method



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Structural and optical properties were studied as a function of films thickness for thermally evaporation PbI₂ films. X-ray diffraction analysis confirmed that PbI₂ films are polycrystalline having hexagonal structure. The optical absorption data indicate an allowed direct transmission with optical energy gap varies continuously from (2.15eV - 2.33 eV). The energy gap shows thickness dependence, which can be explained qualitatively by a thickness dependence of grain size through the decrease of the grain boundary barrier height with grain size. The low fluctuation in energy gap indicates that the grain size is quite small, which is finding in agreement with AFM results.

Keywords: PbI₂; Optical; Structural.

1. INTRODUCTION

Lead iodide PbI₂ is a wide band gap semiconductors E_g ~2.3 eV. Due to the high atomic number of its elements (Z_{Pb}=82, Z_I=53), it is a material with potential use as an ionizing radiation detector (X and γ rays) [1,2,3]. Lead iodide is an important and promising P-type semiconductor and crystallizes in a hexagonal structure and can be grown from solution, vapor and gels [4]. The polytypism of PbI₂ seems to be a significant property of this material with no structure modification. Lead iodide is isostructural to CdI₂ and 20 polytypes have been reported. The poly types of PbI₂ are 2H, 4H, 6H, 8H, 12H, 12R, 14H, 18H, 18R, 20H, 20R, 36H, 42R, 48R. The most common type is 2H, which represents 95% polytypes described for PbI₂ structure [5]. Recently many researches were published on the development of the method of prepared thin films of PbI₂ from solutions, vapor, melts and gels. Similarly to the recently published results reporting on the influence of rare earth (RE) elements on the quality of materials for radiation detectors [6].

Electronic transport and optical measurements in polycrystalline PbI₂ by vacuum evaporation with different thickness and grain size up to 100 nm was studied [7,8]. Conventional vacuum coating unit (INFICON V90) under vacuum of order of 6×10^{-6}

torr with deposition rate of $\sim 4\text{-}7 \text{ nm sec}^{-1}$. A summary of the deposition conditions is shown in table (1). Film thickness was measured after evaporation by optical interferometer method, using He-Ne Laser $\lambda = 0.632 \text{ nm}$ and the thickness were determined. The aim of this work is to prepare a thin polycrystalline lead iodide by vacuum evaporation method, and studying the optical and structural properties of this material to present preliminary results which in this approach could be a way to develop PbI₂ nuclear imaging devices beside the electrical properties.

Table 1 Summary of deposition conditions. [5].

Coating Unit	INFICON V90
Materials	Lead iodide (PbI ₂) powder
Substrates	glass slides
Vacuum	$\sim 6 \times 10^{-6}$ torr
Substrate to film gap	15 cm
Deposition rate	$\sim 4\text{-}7 \text{ nm sec}^{-1}$

2. EXPERIMENTAL DETAILS

Polycrystalline PbI₂ samples were prepared on glass substrates using vacuum evaporation method. PbI₂ powder prepared in the laboratories without further purification as in [9] as checked by X-ray fluorescence the main residual impurity in the base material is Ag as is shown in figure (1). The PbI₂ powder was preheated at temperature $\sim 250 \text{ }^\circ\text{C}$ for several hours to remove occluded materials from it. The prepared material was housed in a vacuum deposition chamber for the preparation of thin film. The E-glass substrate was kept in ambient at 200°C to maintain stoichiometry. At first, a film has been prepared then by decreasing the substrate temperature at a rate $\sim 1\text{K}$ per minute until we brought to room temperature. This process will reduce the defect and grain boundaries if any considerably. The color of the film appears to be pale yellow in nature. The evaporation was carried out.

3. RESULTS AND DISCUSSION

X-ray diffraction analyses of all the films with different thickness show a high degree of crystallite orientation with the basal plane parallel to substrate and c-axis normal to the substrate plane indicated by the negligible relative intensity of (002), (003) and (004) reflection. X-ray diffraction (XRD) pattern of the films deposited on glass substrate in a "Shimadzu XRD 6000". Advance using Cu-K radiation of monochromatic wavelength.

For pure PbI₂ films recorded for a range of 2 from 10° to 60° at 2° glancing angle. Figure (2:A,B,C,D) shows a typical XRD of a thin film of lead iodide samples. The inter-planer distance d and (hkl) planes are shown in table (2), which corresponds to XRD and standard ASTM data [10], the main facts of all XRD patterns are the existence of the same peaks through different deposition conditions.

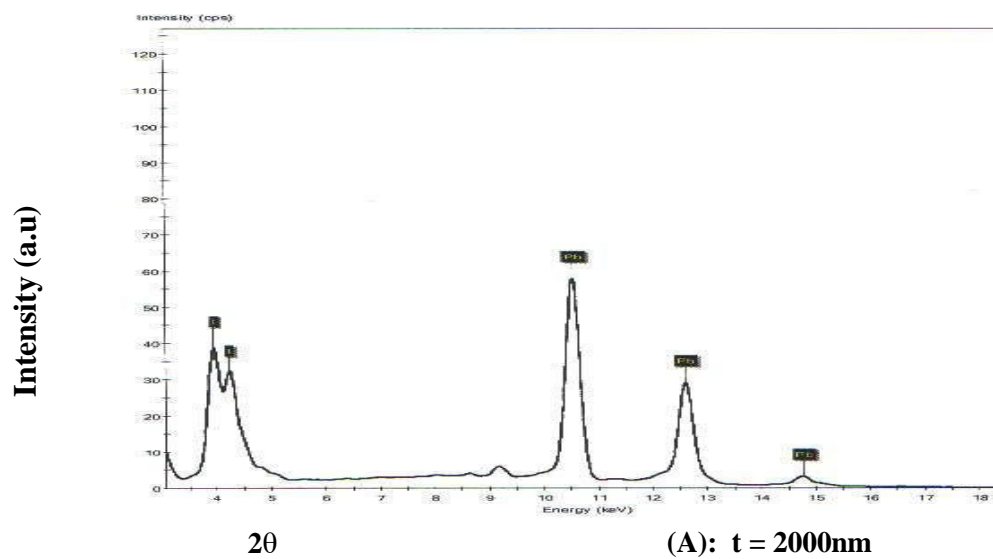
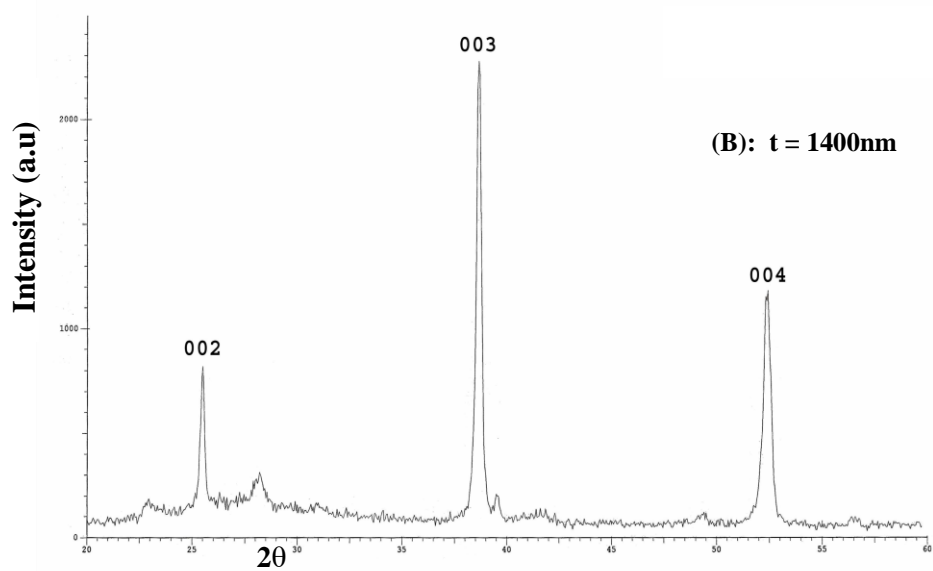


Figure 1 X-ray fluorescence pattern of PbI₂



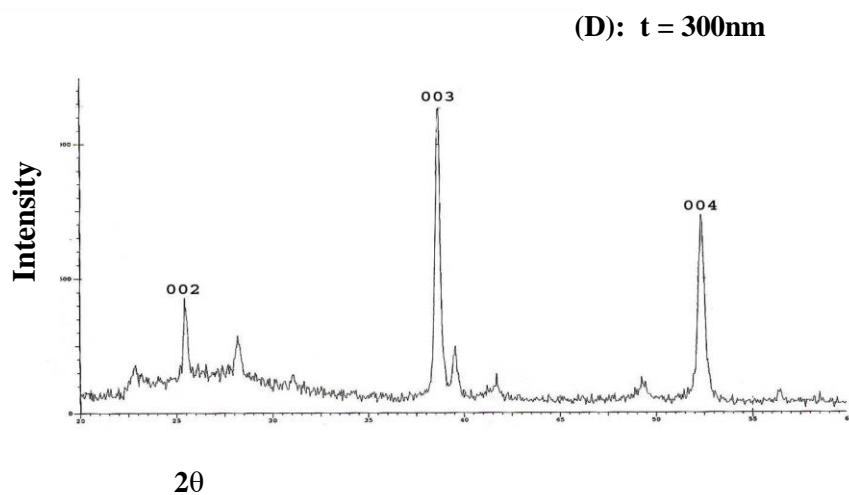
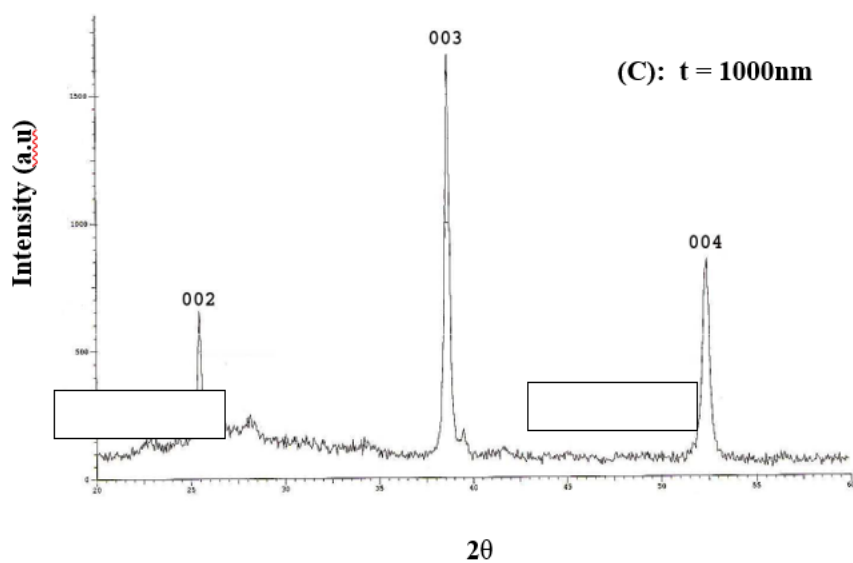


Figure 2 X-Ray diffraction pattern and miller indices of PbI_2 films prepared with different thickness

Table 2 Structural values of PbI₂ thin films at different thickness with ASTM.

Thickness nm	2	d (A°) Observed	d (Ao) ASTM	hkl	δ	FWHM (deg.)	Average G.S(nm)
300	25.5126	3.4886	3.4890	002	0.011	0.2455	36.7303
	38.6567	2.3260	2.3270	003	0.043	0.2777	
	52.362	1.7458	1.74490	004	0.114	0.3401	
1000	25.5221	3.48733	3.4890	002	0.057	0.24110	39.4976
	38.6581	2.32520	2.3270	003	0.077	0.25760	
	52.3631	52.3631	1.74490	004	0.16	0.34820	
1400	25.5476	3.48390	3.4890	002	0.171	0.21590	43.6354
	38.7002	2.3250	2.3270	003	0.086	0.2323	
	52.4105	1.74439	1.74490	004	0.057	0.2538	
2000	25.4951	3.4909	3.4890	002	0.054	0.2527	46.4670
	38.6434	2.32469	2.3270	003	0.103	0.21797	
	52.348	1.74632	1.74490	004	0.172	0.3795	

A comparison between our results and those of the ASTM standard data is shown in table (2). It is clear that a strong peak is observed at ($d= 3.486, 2.332$ and 1.744 \AA^0) which corresponds to the reflection planes (002), (003) and (004) respectively. These results are agreed well with data achieved by others [1,3]. An accurate observation of each reflection peak for most samples reveals the presence of two less intense peaks very close to the main one (30-40⁰). This is probably due to the presence of polytypes [10,11]. As shown in figure (3A,B) an AFM(Atomic force micrograph) model (AA3000) scanning prop microscope was used in this search, the AFM Where G.S is the average grain size is the X-ray wavelength, $\Delta(2\theta)$ is (FWHM), θ Bragg diffraction angle of XRD peak (degree). Figure (4) shows the variation in the average grain size with different thickness. Average grain size increases linearly with increasing thickness. The increasing tensile stress as it seen in figure (3) may be responsible for the flattening of grains.

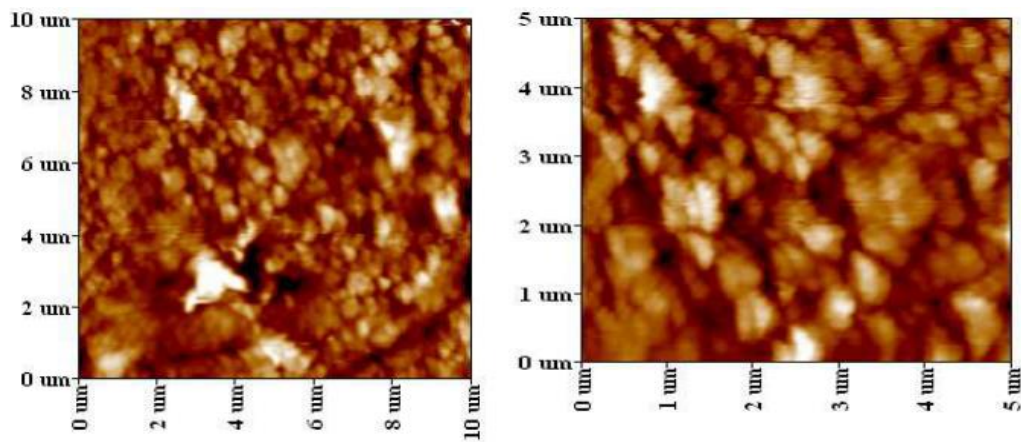


Figure 3 AFM photograph of PbI₂ films at thickness (A) 1000nm and (B) 2000 nm

In the X-ray diffraction data, we have directly measured $\Delta(2\theta)$ for major peaks of appreciable relative intensities we can calculate [14], results show very smooth surfaces for both 1000 nm and 2000 nm thickness, $[d_{ASTM} / d_{XRD} / d_{ASTM}] 100\%$ (1)

with an average surface roughness of 23nm for 1000nm thickness and 19.1nm for 2000nm thickness. Also different in grains area with different thickness, in thickness 1000nm the grains area seems smaller than in the case of 2000nm thickness.

The X-ray diffraction data can also be used to determined residual stress or non-uniform strain in the film due to structural defects like dislocation, stacking faults, which are quite common in the films grown by thermal evaporation. The in homogeneous stress in the film can be determined from the line broadening $\Delta(2\theta)$, full width at half maximum (FWHM) (Where 2θ is the diffraction angel), which is also related to the variation in d spacing (where d is the distance between any two parallel crystal planes having the same Miller index (hkl) through a relation [12].

The residual stress may increase with film thickness depending mainly on the depositing material and growth conditions [13]. Different materials show different behaviors. However, the linear dependence of d/d on film thickness observed for PbI₂ films could be due to the orientation crystallite growth.[15].

The optical transmission spectra of PbI₂ films deposited on the glass substrate at different thickness was recorded as a function of wavelength in the range of (380-900) nm at room temperature it shown in the figure (6). The average transmission over the rang

$$\Delta(2\theta) = 2 \tan \theta \tag{2}$$

(380-900) nm exceeds 85% with a sharp fall near the fundamental absorption; The average grain size is determined from the full width at half maximum (FWHM) for the most intense peak using the Scherrers formula [13], whereas fall in transmission is gradual for other samples, these results are good agreement with the measurements results obtained by T.Ghosh et al [16]

The absorption coefficient (α) was calculated using Lambert law as follows [14]:

$$\ln(I_0/I) = 2.303A = \alpha d \tag{3}$$

where I_0 and I are the intensity of incident light and transmission light respectively, A is the optical absorbance and d the sample thickness. The absorption coefficient (α) was found to follow the relation:

$$\alpha = [G(h\nu - E_g)^{1/2}] / h\nu \tag{4}$$

where G is a constant and E_g the optical energy gap, figure (7) shows the relation between absorption coefficient and photon energy. Plots of $(\alpha h\nu)^2$ versus the photon energy (hν) in the absorption region near the fundamental absorption edge indicate direct allowed transmission in the film material, as shown in figure (8). The optical energy gap was estimated from the extrapolation of the linear portion of the graph to the photon energy axis [17]. It is observed that E_g decreases with increasing thickness as it shown in figure (9). The interface between the substrate and films is an important junction where free energy supplied and minimizing it by a slow process shall reduce the chance of formation of decades, and the grain size[5]. In general, thickness dependence of optical band gap can arise due to one or combined effect of the change in barrier height due to change in grain size in polycrystalline films as given in Table 3 [18].

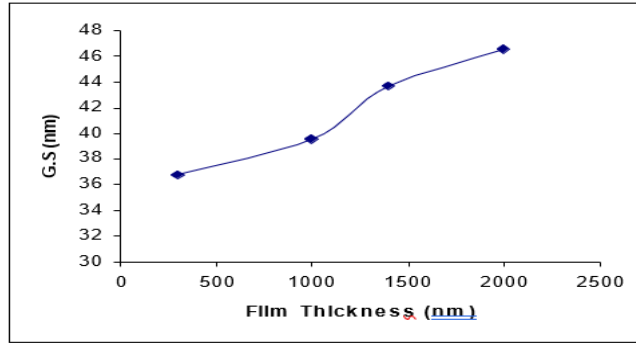


Figure 4 Grain size with film thickness of PbI_2

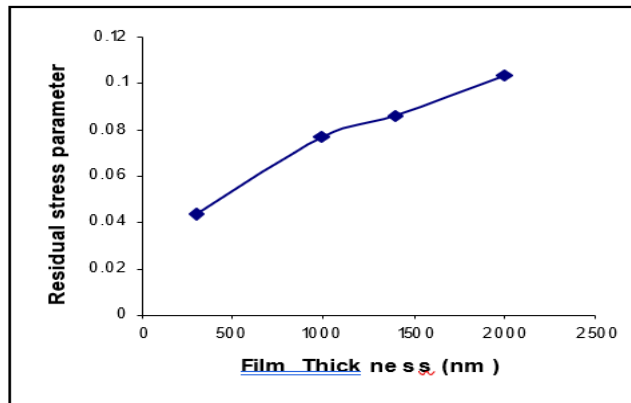


Figure 5 Residual stress with film thickness of PbI_2

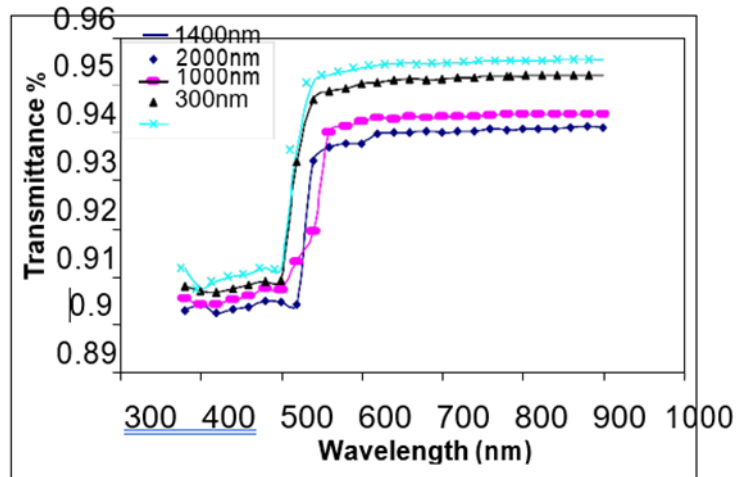


Figure 6 Optical transmittance spectra for different thickness of PbI_2

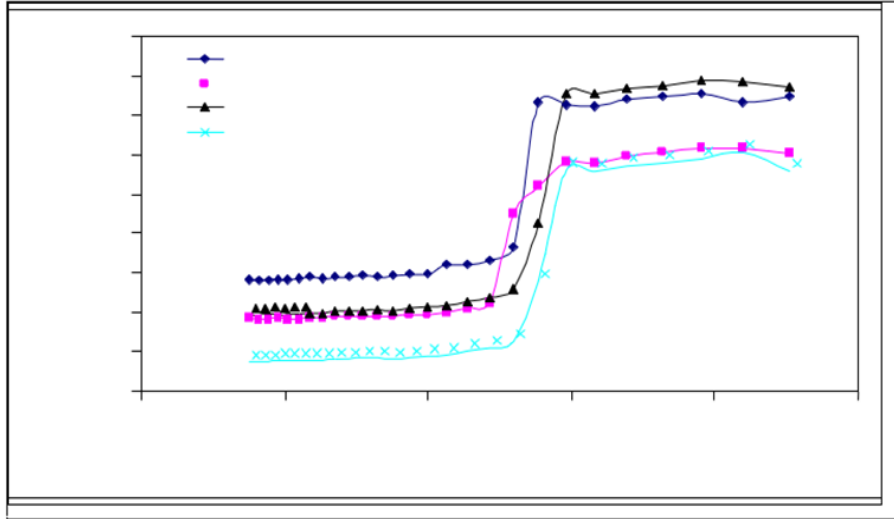
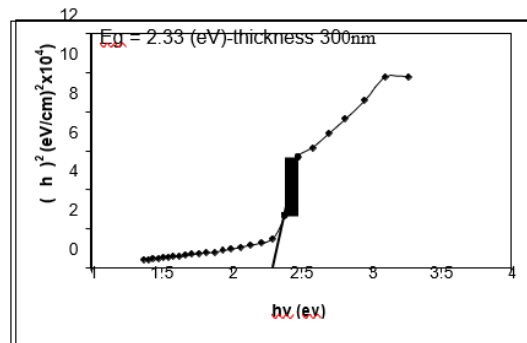
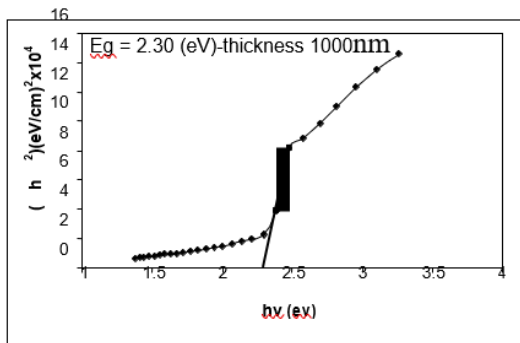


Figure 7 Absorption coefficient as a function of h for PbI_2 films with different thickness

Table 3 Values of band gap for different thickness of PbI_2



Thickness (nm)	Band gap (eV)
300	2.33
1000	2.3
1400	2.24
2000	2.15

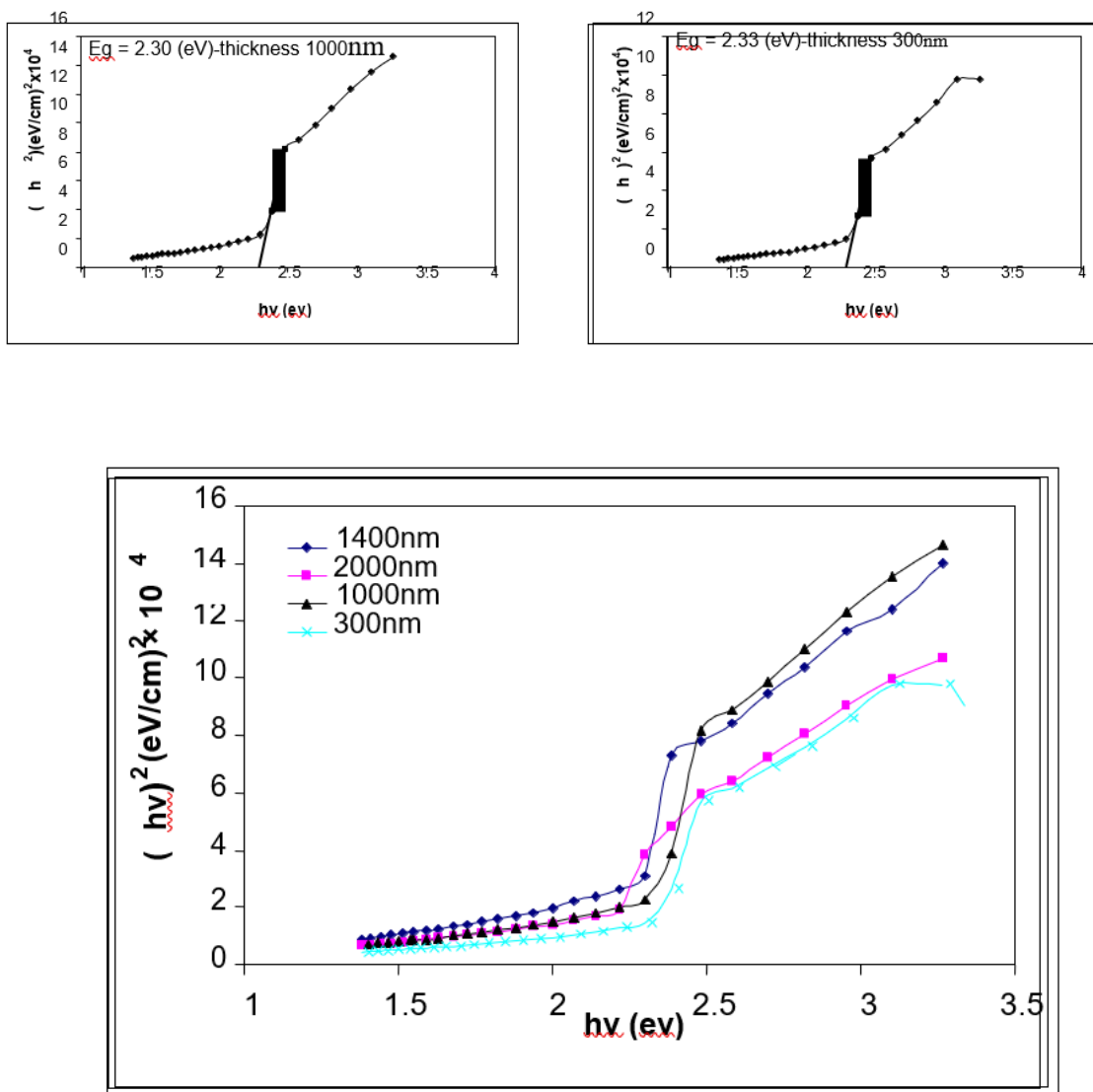


Figure 8 Photon energy dependences of the absorption coefficient squared for PbI₂ films with different thickness to determine of E_g

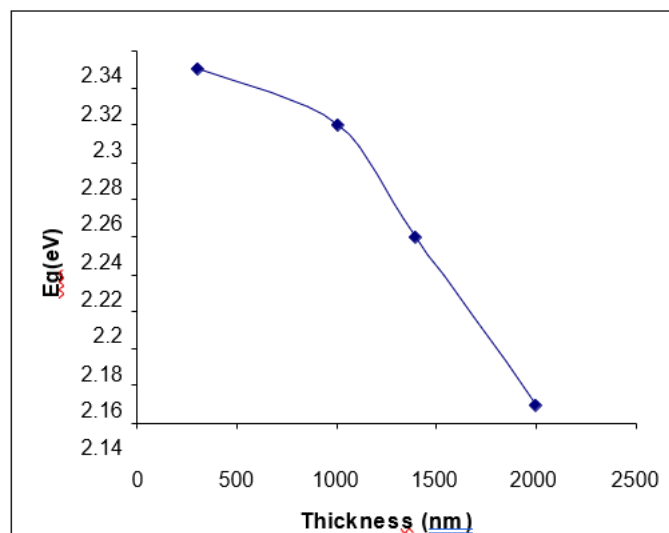


Figure 9 Film thickness dependence on direct optical energy gap for PbI_2 films

4. CONCLUSIONS

The X-ray diffraction analysis confirms that PbI_2 films are polycrystalline, having a hexagonal structure. The inception of the data for pure thin film of lead iodide indicates that the observed (d) values closely matched with the existing standard values for hexagonal structure. The low fluctuation in the value of structure parameters is due to the fluctuation in lattice parameters, which is attributed to the stress (positive) that accompanies the increase in grain size. The values of the band gap vary from (2.15 eV– 2.33 eV). The low fluctuation in energy gap with sample thickness indicates that the grain size is quite small. The results are in agreement with the existing works adopting different techniques for film preparation. The reproducibility in making thin films of PbI_2 is very good by the present method.

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